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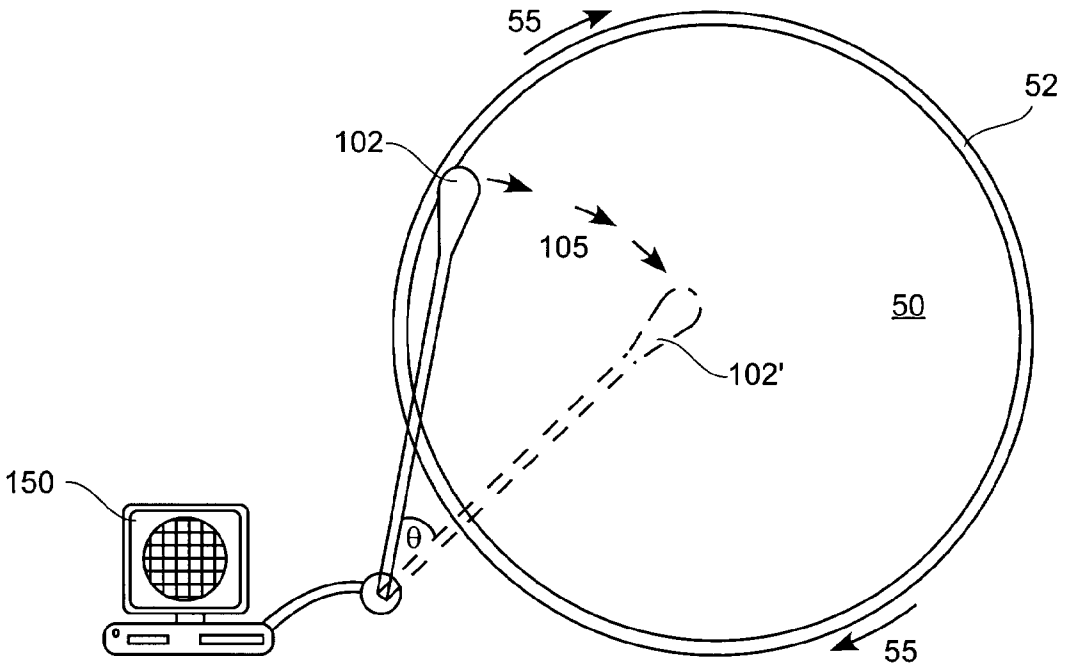
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(54) **Title:** METHOD AND APPARATUS FOR MEASUREMENT OF THIN FILMS AND RESIDUES ON SEMICONDUCTOR SUBSTRATES



(57) **Abstract:** A method of sensing properties of materials on a substrate is provided. The method includes scanning along a path defined over a surface of a substrate that can have a film. The substrate is configured to spin when present. The method includes sensing properties of the film at a plurality of points along the path and generating a map of the film using information from the plurality of points along the path. An apparatus for sensing properties of materials on a substrate is also provided.

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